

LECTURE NOTES

INTENSIVE COURSE - CLTPP-3

SOCRATES

Course on Low Temperature Plasma Physics and Applications

Eindhoven, The Netherlands

July 8-14, 1998

Master Class on Surface and
Volume Reactions in Molecular Plasmas
July 15-17, 1998

Support:



CENTRUM VOOR PLASMAFYSICA EN STRALINGSTECHNOLOGIE

Graduiertenkolleg HTPP

Arbeitsgemeinschaft Plasmaphysik (APP)

Stichting voor Fundamenteel Onderzoek der Materie (FOM)

Technologiestichting STW

PROGRAM OF THE COURSE:

Wednesday, July 8:

- 08.15 - 08.45 Student registration
- 08.45 - 09.15 Welcome and short introduction
M. van der Wiel
- 09.15 - 10.45 Introduction, gas discharge, plasmas, applications, plasma types, similarities (E/N, pd), stability
N. St.J. Braithwaite
- 11.15 - 12.45 Fundamentals, Debye character, collisions with neutrals, coulomb collisions, inelastic collisions, ionisation, excitation mean free paths, time constants, magnetic field confinement, Hall parameters, cyclotron resonance.
D.C. Schram
- 14.00 - 15.30 Electron kinetics, processes, electron energy distributions (incl. Maxwell...), transport properties
J. Loureiro
- 16.00 - 17.30 Excitation and radiation in atomic plasma, collisional radiative models,
J.A.M. van der Mullen.

Thursday, July 9:

- 09.00 - 10.30 Plasma production, plasma sources:
DC glow, RF plasma capacitive, inductive, surfatron, helicon, ECR, microwave plasmas
M. Schmidt
- 11.00 - 12.30 RF discharges, electron distribution functions, D.C. potentials, ion energy distribution, charge exchange collisions.
W.J. Goedheer
- 14.00 - 15.30 RF discharges, electron kinetics, particle in cell/ Monte Carlo models
S. Longo
- 16.00 - 17.30 Hydrodynamic models, numerical problems.
W.J. Goedheer

Friday, July 10:

- 09.00 - 10.30 Thermal plasmas, fundamentals, characteristic lengths, distribution functions, equilibrium, radiation etc..
P. Fauchais
- 11.00 - 12.30 Thermal plasmas, generation, arcs etc., RF discharges, inductive, capacitive torch design.
P. Fauchais
- 14.00 - 15.30 Application, cutting, welding etc..
P. Fauchais
- 16.00 - 17.30 Radiation and spectroscopy in thermal plasmas
V. Helbig

Saturday, July 11:

09.00 - 10.30 Kinetics in molecular plasmas, dissociation, ro-vibrational excitation, influence on charge density and distribution functions
J.Loureiro

11.00 - 12.30 Electron kinetics, processes in H₂, N₂ (O₂) plasmas
A. Ricard

Saturday afternoon free for shopping etc..

Sunday, July 12: Excursion/day off**Monday, July 13:**

09.00 - 10.30 Surface processes, sputtering (physical and chemical), reflection, absorption, desorption polymerisation, abstraction.
A. van Keudell

11.00 - 12.30 Mass spectrometry. Residual gas analysis probes.
Ch. Hollenstein

14.00 - 15.30 Plasma diagnostics I
interferometry, emission and absorption spectroscopy (Fourier Transform).
Ch. Hollenstein

16.00 - 17.30 Plasma diagnostics II
Thomson scattering, Rayleigh scattering, CARS
H. Kempkens

Tuesday, July 14:

09.00 - 10.30 Plasma diagnostics III
TALIF, VUV spectroscopy
H.F. Döbele

11.00 - 12.30 Plasma diagnostics IV
LIF, velocity measurements, cavity ringdown
N. Sadeghi

14.00 - 15.30 Radical interactions, infrared spectroscopy
G.M.W. Kroesen

16.00 - 17.30 Ion neutral synergisme during plasma etching and deposition
M.C.M. van de Sanden

17.30 - 18.00 Conclusions, summing up, closure.

PROGRAM OF THE MASTER CLASS:

Wednesday, July 15:

- 09.00 - 10.30 Modelling of (non-equilibrium) plasmas (plasma display)
J.P. Boeuf
- 11.00 - 12.30 Negative ion formation, surface and volume reactions
W. Stoffels
- 14.00 - 15.30 Formation of (metastable) molecules in N₂/O₂ plasmas
J. Marec
- 16.00 - 17.30 Negative hydrogen ion formation and the importance of H₂(r,v)
B.J. Graham
- 20.00 - 21.30 Discussion session, student contributions at the motel
Eindhoven

Thursday, July 16:

- 09.00 - 10.30 In-situ analysis of surface reactions
A. van Keudell
- 11.00 - 12.30 Measurements of radicals and generated molecules
N. Sadeghi
- 14.00 - 15.30 Modelling of plasma deposition of a-Si:H
W. Goedheer
- 16.00 - 17.30 Nucleation in plasmas and powder formation
A. Bouchoule

Friday, July 17

- 08.30 - 10.00 Deposition mechanisms, a-C deposition
W. Jacob
- 10.30 - 12.00 Mechanisms of a-Si:H deposition
M.C.M. van de Sanden
- 12.00 - 12.45 Discussion on subjects master class and closure.
- 12.45 - 14.00 Lunch.